

Title (en)
METHOD FOR PROCESSING, IN PARTICULAR SEPARATING, A SUBSTRATE BY MEANS OF LASER-INDUCED DEEP REACTIVE ETCHING

Title (de)
VERFAHREN ZUR BEARBEITUNG, INSBESONDERE ZUM TRENNEN EINES SUBSTRATES MITTELS LASERINDUZIERTEM TIEFENÄTZEN

Title (fr)
PROCÉDÉ D'USINAGE, EN PARTICULIER DE SÉPARATION, D'UN SUBSTRAT PAR GRAVURE PROFONDE INDUITE PAR LASER

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Application
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Priority

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Abstract (en)
[origin: WO2018210484A1] The invention relates to a method for processing a substrate by means of laser-induced deep reactive etching, wherein the laser radiation is moved along a processing line and individual pulses with a spatial laser pulse distance (d) are directed towards the substrate. An anisotropic material removal is then performed by means of etching at an etching rate (R) and an etching duration (t) under the condition $1 > d/(R \cdot t) > 10^{-5}$.

IPC 8 full level
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Citation (examination)

- WO 2017038075 A1 20170309 - NIPPON SHEET GLASS CO LTD [JP]
- WO 2015018425 A1 20150212 - TRUMPF LASER & SYSTEMTECHNIK [DE]
- US 2014248757 A1 20140904 - MORIKAZU HIROSHI [JP], et al
- See also references of WO 2018210484A1

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RU2756175C1

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